

IN THE CLAIMS

Claims 1-23 (Cancelled)

Claim 24 (New) A method for producing an organic EL display element, comprising forming an insulating layer from a radiation sensitive composition comprising an alkali-soluble resin having no epoxy group, a 1,2-quinonediazide compound, and at least one compound selected from the group consisting of a melamine compound and an epoxy compound overlying a substrate, and

forming an organic EL emitting layer overlying the insulating layer.

Claim 25 (New) The method of Claim 24, wherein the alkali-soluble resin is a novolak resin having no epoxy group.

Claim 26 (New) The method of Claim 24, wherein the alkali-soluble resin is a copolymer having no epoxy group of (1a) at least one unsaturated monomer selected from the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (2a) an olefinic unsaturated monomer other than unsaturated monomer (1a).

Claim 27 (New) The method of Claim 24, wherein said composition comprises a melamine compound.

Claim 28. (New) The method of Claim 24, wherein said composition comprises an epoxy compound.

Claim 29. (New) The method of Claim 24, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide.

Claim 30. (New) The method of Claim 27, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide and wherein the alkali-soluble resin is a copolymer having no epoxy group of (1a) at least one unsaturated monomer selected from the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (2a) an olefinic unsaturated monomer other than unsaturated monomer (1a).

Claim 31. (New) The method of Claim 28, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide and wherein the alkali-soluble resin is a copolymer having no epoxy group of (1a) at least one unsaturated monomer selected from the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (2a) an olefinic unsaturated monomer other than unsaturated monomer (1a).

Claim 32 (New) An organic EL display element comprising an organic EL emitting layer and an insulating film formed from a radiation sensitive composition comprising an alkali-soluble resin having no epoxy group, a 1,2-quinonediazide compound, and at least one compound selected from the group consisting of a melamine compound and an epoxy compound.

Claim 33 (New) The element of Claim 32, wherein the alkali-soluble resin is a novolak resin having no epoxy group.

Claim 34 (New) The element of Claim 32, wherein the alkali-soluble resin is a copolymer having no epoxy group of (1a) at least one unsaturated monomer selected from the

group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (2a) an olefinic unsaturated monomer other than unsaturated monomer (1a).

Claim 35 (New) The element of Claim 32, wherein said composition comprises a melamine compound.

Claim 36. (New) The element of Claim 32, wherein said composition comprises an epoxy compound.

Claim 37. (New) The element of Claim 32, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide.

Claim 38. (New) The element of Claim 35, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide and wherein the alkali-soluble resin is a copolymer having no epoxy group of (1a) at least one unsaturated monomer selected from the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (2a) an olefinic unsaturated monomer other than unsaturated monomer (1a).

Claim 39. (New) The element of Claim 36, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide and wherein the alkali-soluble resin is a copolymer having no epoxy group of (1a) at least one unsaturated monomer selected from the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and

phenolic hydroxyl group-containing unsaturated monomer, and (2a) an olefinic unsaturated monomer other than unsaturated monomer (1a).

Claim 40. (New) A method for producing an organic EL display element, comprising forming an insulating layer from a radiation sensitive composition comprising (a') an alkali-soluble resin having an epoxy group and (b) a 1,2-quinonediazide compound overlying a substrate, and

forming an organic EL emitting layer overlying the insulating layer.

Claim 41. (New) The method of Claim 40, wherein the alkali-soluble resin having an epoxy group is a copolymer having an epoxy group of (1a) an unsaturated monomer having an epoxy group, (2a) at least one unsaturated monomer selected from the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (3a) an olefinic unsaturated monomer other than unsaturated monomers (1a) and (2a).

Claim 42. (New) The method of Claim 40, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide.

Claim 43. (New) The method of Claim 41, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide.

Claim 44. (New) An organic EL display element comprising an organic EL emitting layer and an insulating film formed from a composition comprising an alkali-soluble resin having no epoxy group and a 1, 2-quinonediazide compound.

Claim 45. (New) The element of Claim 44, wherein the alkali-soluble resin having an epoxy group is a copolymer having an epoxy group of (1a) an unsaturated monomer having an epoxy group, (2a) at least one unsaturated monomer selected from the group consisting of an unsaturated carboxylic acid, unsaturated carboxylic anhydride and phenolic hydroxyl group-containing unsaturated monomer, and (3a) an olefinic unsaturated monomer other than unsaturated monomers (1a) and (2a).

Claim 46. (New) The element of Claim 44, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide.

Claim 47. (New) The element of Claim 45, wherein said 1,2-quinonediazide compound is selected from the group consisting of a 1,2-benzoquinonediazidesulfonic acid ester, 1,2-naphthoquinonediazidesulfonic acid ester, 1,2-benzoquinonediazidesulfonamide, and 1,2-naphthoquinonediazidesulfonamide.

Claim 48. (New) The method of Claim 24, wherein said radiation sensitive composition further comprises (c) a basic nitrogen-containing compound.

Claim 49. (New) The element of Claim 32, wherein said radiation sensitive composition further comprises (c) a basic nitrogen-containing compound.